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INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT: John Bruley et al.	
(Use several sheets if necessary) (37 CFR 1.98(b))		FILING DATE:	GROUP: 2818

## REFERENCE DESIGNATION

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB-CLASS	FILING DATE IF APPROPRIATE
AA						
AB						
AC						
AD						
AE						
AF						
AG						
AH						
AI						

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB-CLASS	TRANSLATION YES	NO
AI							
AK							
AL							

## OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

PD A	AM	Two Dimensional Mapping of the Electrostatic Potential in Transistors by Electron Holography, W.D. Rau, P. Schwander, F.H. Baumann, W. Hopfner, and A. Ourmazd, The American Physical Society, Vol. 82, No. 12, March 1999, pp. 2614-2617.
	AN	Electron Holography of Semiconductor Structures: Principles and Recent Results, Michael A. Gribelyuk, Martha R. McCartney, Microelectronic Failure Analysis Desk Reference 2002 Supplement Copyright® 2002. ASM International®, pp.69-74.
	AO	Focused Ion Beam Milling for Site Specific Scanning and Transmission Electron Microscopy Specimen Preparation, L.A. Giannuzzi, J.L. Drown, S.R. Brown, R.B. Irwin, and F.A. Stevie, pp. 347-348.
	AP	FIB Lift-Out for Defect Analysis, Lucille A. Giannuzzi, Brian W. Kemphall, Shawn D. Anderson, Brenda I. Prenitzer, and Thomas M. Moore, Microelectronic Failure Analysis Desk Reference 2002 Supplement. Copyright® 2002. ASM International®, pp.29-35.
	AQ	Mapping of Electrostatic Potential in Deep Submicron CMOS Devices by Electron Holography, M.A. Gribelyuk, M.R. McCartney, Jing Li, C.S. Murthy, P. Ronshelm, B. Doris, J.S. McMurray, S. Hegde and David J. Smith, The American Physical Society, Vol. 89, No. 2, July 2002, pp.1-4.
PD	AR	Visualisation of Electrically Active Areas Using Electron Holography, U. Muehle, A. Lenk, M. Lehmann and H. Lichte, Proceedings from the 28th International Symposium for Testing and Failure Analysis, 3-7 November, 2002, pp. 39-45.

EXAMINER

PHUC T. DANG

DATE CONSIDERED

11/12/2004

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and